Physics of EUV and Short Wavelength 1:30 8:45 AM 10:15 AN Sources with Focus on Atomic Physics 0:15 10:15 AM 10:30 AM 12:00 PN	# Paper #	Area	Presenter	Company	Title	Duration	Start	Finish		
Short Course 8:30 AM, Sunday, June 2, 2024, Berkeley, CA (Course is held online Only) All Times are for Berkeley, CA, USA. Please estimate times for your own time zones. It is a live event. Short Course: EUV and Soft X-Ray Sources Instructors: Gerry O'Sullivan, Marcelo Ackermann, Henry Kapteyn and Bjorn Hegelich EUVL Short Courses and EUVL Workshop require separate registrations. Please visit www.euvlitho.com for information. AV Test and Speaker Check-in Physics of EUV and Short Wavelength Sources with Focus on Atomic Physics Break UC Berkeley UC Berkeley Univ of Colorado and Henry C. Kapteyn K&M Labs UT Austin and UT Austin and Laser-driven accelerators and coherent EUV 1:30 2:15 PM 3:45 PM 3:			All Times ar	e local time in	Berkeley, CA, USA (PDT)					
Short Course 8:30 AM, Sunday, June 2, 2024, Berkeley, CA (Course is held online Only) All Times are for Berkeley, CA, USA. Please estimate times for your own time zones. It is a live event. Short Course: EUV and Soft X-Ray Sources Instructors: Gerry O'Sullivan, Marcelo Ackermann, Henry Kapteyn and Bjorn Hegelich EUVL Short Courses and EUVL Workshop require separate registrations. Please visit www.euvlitho.com for information. AV Test and Speaker Check-in Physics of EUV and Short Wavelength Gerry O'Sullivan UCD Sources with Focus on Atomic Physics Break UCS Berkeley UN Multilayers UN Multilayers Univ of Colorado and Henry C. Kapteyn K&M Labs High Harmonic EUV Sources Break UT Austin and UT Austin and UT Austin and UN Sources is held online Only All Tevense is held online Only All Time are for Berkeley vent. Short Course is held online Only All Time are for Berkeley vent. Short Course is held online Only All Time are for Berkeley alive event. Short Course is held online Only All Time are for Berkeley alive event. Short Course is held online Only All Time are for Berkeley. It is a live event. Short Course is held online Only All Time are for Berkeley. It is a live event. Short Course event. Short Course is held online Only Break 0:15 a live event. Short Course event. Short Course event. Short Course for Message visit www.euvlitho.com for information. Break 0:15 a live event. Short Course event	On June	2, 2024 Short Courses	is on-line only. June 3 Sl	hort Course is i	in a Hybrid format. From June 4-6, 2024 w	vorkshop	is in-perso	n only.		
8:30 AM, Sunday, June 2, 2024, Berkeley, CA (Course is held online Only) All Times are for Berkeley, CA, USA. Please estimate times for your own time zones. It is a live event. Short Course: EUV and Soft X-Ray Sources Instructors: Gerry O'Sullivan, Marcelo Ackermann, Henry Kapteyn and Bjorn Hegelich EUVL Short Courses and EUVL Workshop require separate registrations. Please visit www.euvlitho.com for information. AV Test and Speaker Check-in Physics of EUV and Short Wavelength Gerry O'Sullivan UCD Sources with Focus on Atomic Physics Break UC Berkeley UNIV of Colorado and Henry C. Kapteyn Henry C. Kapteyn UT Austin and Laser-driven accelerators and coherent EUV 1:30 2:15 PM 3:45 PM 1:30 10:30 AM 12:30 PM 1:30 12:30 PM 2:15 PM 3:45 PM 3:45 PM 3:45 PM 3:45 PM		Ve	ersion: June 5, 2024 . For a	questions or con	nments please contact info@euvlitho.com			-		
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Break 0:15 10:15 AM 10:30 AM Marcelo Ackerman UC Berkeley EUV Multilayers Lunch Break 0:30 12:00 PM 12:30 PM Univ of Colorado and K&M Labs High Harmonic EUV Sources Break 0:15 10:15 AM 10:30 AM 12:00 PM 1:30 12:30 PM 2:00 PM 1:30 12:30 PM 2:00 PM 1:30 12:30 PM 2:00 PM 1:30 12:30 PM 2:15 PM 1:30 2:15 PM 3:45 PM					,	1:30	8:45 AM	10:15 AM		
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Univ of Colorado and Fundamentals and Applications of Coherent K&M Labs High Harmonic EUV Sources Break 0:15 2:00 PM 2:00 PM 0:15 PM			Iviarceio Ackerman	OC Berkeley	•	0.20	12:00 DM	12.20 DM		
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			Bjorn Manuel Hegelich	Tau Systems	and X-ray Sources					
Short Course Adjourned				Shart Ca	Alternation					



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# P	aper #	Area	Presenter	Company	Title	Duration	Start	Finish
				Short C	Course			
8:3	30 AM,	Monday, June 3, 2024	I, Berkeley, CA (Course i	s held in hybrid	d mode. All instructors will be in-person a	at LBNL, B	LDG 66 - R	m 316)
			Short C	Course: E	UV Lithography			
Ins	structo	ors: Vivek Bakshi (E	UV Litho, Inc.), Patri	ick Naulleau	(CXRO), Sangsul Lee (Postiche Unive	ersity),		and
				Jan van Sho	oot (ASML)			
	EU	VL Short Courses ar	nd EUVL Workshop re	quire separate	e registrations. Please visit www.euvlitho	.com for i	nformation	1.
					Breakfast, AV Test and Speaker Check-in	0:15		
						1:30	8:45 AM	10:15 AM
			Vivek Bakshi	EUV Litho Inc.	Introduction to EUVL and EUV Sources			
			VIVER DAKSIII	LOV LITTIO IIIC.	Break	0.15	10:15 AM	10·30 AM
							10:30 AM	
				POSTECH and				
			Sangsul Lee	PAL	EUVL Masks			
					Lunch Break	1:00	12:00 PM	1:00 PM
						1:30	1:00 PM	2:30 PM
			Patrick Naulleau	EUV Tech	EUVL Patterning and Resist			
					Break	0:15	2:30 PM	2:45 PM
						1:30	2:45 PM	4:15 PM
			Jan van Schoot	ASML	High NA EUVL			
				Short Course	Adjourned			



# Paper #	Area	Presenter	Company	Title	Duration	Start	Finish

2024 EUVL Workshop and Supplier Showcase

Please see Abstract Book on website www.euvlitho.com for abstracts and co-author(s) information by paper #.

9:30 AM, Tuesday, June 4, 2024, LBNL, CA (Workshop held in-person only, Building 66, Room 317)

Sessions 1 - 2: LBNL and Supplier Program Showcase

Session 1: LBNL Program Showcase; Session Chair: Ricardo Ruiz (LBNL) and Bruno La Fontaine (LBNL)

				7			
					1:00	9:30 AM	10:30 AM
				AV Test, Speaker Check-in, Breakfast,			
				Coffee and Registration			
					0:10	10:30 AM	10:40 AM
		Vivek Bakshi / Patrick	EUV Litho /				
	Introduction	Naulleau	EUV Tech	Welcome and Announcements			
					0:30	10:40 AM	11:10 AM
1 P7	Keynote	John Shalf	LBNL	Computing Beyond Moore's Law			
					0:15	11:10 AM	11:25 AM
				A Holistic Approach to Patterning Science			
2 P106	LBL Showcase	Ricardo Ruiz	LBNL	at Berkeley Lab			
					0:15	11:25 AM	11:40 AM
2 P102	LBL Showcase	Maurice Garcia-Sciveres	LBNL	Nanoscale Photon Sensing			
					0:15	11:40 AM	11:55 AM
2 P105	LBL Showcase	Paul Ashby	LBNL	Spatially Resolved EUV Resist Dissolution			
				Characterization of Chemical/structural	0:15	11:55 AM	12:10 PM
				Information of Latent Image via Critical-			
2 P103	LBL Showcase	Cheng Wang	LBNL	dimension Resonant Soft X-ray Scattering			



Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
				Multimodal characterization of electrons	0:15	12:10 PM	12:25 PM
				and excitons in 2D materials and their			
P107	LBL Showcase	Archana Raja	LBNL	heterostructures			
					1:05	12:25 PM	1:30 PM
				Lunch			
	Sess	ion32: Supplier Program	Showcase; Sessio	n Chair: Take Watanabe (University of Hyogo)		
					0:15	1:30 PM	1:45 PM
P81	Supplier Showcase -1	Richard Ciesielski	PTB	Synchrotron-based EUV metrology at PTB			
					0:15	1:45 PM	2:00 PM
		Jacqueline van		TNO EUV Materials Research for EUV			
P85	Supplier Showcase -1	Veldhoven	TNO	Infrastructure			
					0:15	2:00 PM	2:15 PM
P88	Supplier Showcase -1	Bruno La Fontaine	LBNL	EUVL Capabilities at CXRO			
					0:20	2:15 PM	2:35 PM
				Coffee Break			
	Session 4:	Supplier Showcase -2; S	ession Co-Chairs: I	Meng Lee (Veeco) and Matt Hettermann (EUV	Tech)		
				Veeco Ion Beam Deposition Advancement	0:15	2:35 PM	2:50 PM
				and Diamond Like Carbon as Novel Material			
P86	Supplier Showcase -2	Meng Lee	Veeco	for EUV Mask Blanks (Invited)			
					0:15	2:50 PM	3:05 PM
				Yield Relevant Patterning Control For Next			
P87	Supplier Showcase -2	JeongHo Yeo	AMAT	Generation Device Technology			
				Preparing the Availability of EUV Light	0:15	3:05 PM	3:20 PM
				Sources for High Volume Manufacturing			
P83	Supplier Showcase -2	Henry Chou	Energetiq	(Invited)			
					0:15	3:20 PM	3:35 PM
P82	Supplier Showcase -2	Matt Hettermann	EUV Tech	Applications of EUV Metrology Tools			
	P107 P81 P85 P88 P86 P87	P107 LBL Showcase Sess P81 Supplier Showcase -1 P85 Supplier Showcase -1 P88 Supplier Showcase -1 Session 4: P87 Supplier Showcase -2 P87 Supplier Showcase -2 P88 Supplier Showcase -2 P88 Supplier Showcase -2	Session 32: Supplier Program P81 Supplier Showcase -1 Richard Ciesielski P85 Supplier Showcase -1 Veldhoven P88 Supplier Showcase -1 Bruno La Fontaine Session 4: Supplier Showcase -2; S P86 Supplier Showcase -2 Meng Lee P87 Supplier Showcase -2 JeongHo Yeo P88 Supplier Showcase -2 Henry Chou	Session 32: Supplier Program Showcase; Sessio P81 Supplier Showcase -1 Richard Ciesielski PTB Jacqueline van Veldhoven TNO P88 Supplier Showcase -1 Bruno La Fontaine LBNL Session 4: Supplier Showcase -2; Session Co-Chairs: I P86 Supplier Showcase -2 Meng Lee Veeco P87 Supplier Showcase -2 JeongHo Yeo AMAT P88 Supplier Showcase -2 Henry Chou Energetiq	Multimodal characterization of electrons and excitons in 2D materials and their heterostructures Lunch Session32: Supplier Program Showcase; Session Chair: Take Watanabe (University of Hyogo P81 Supplier Showcase -1 Richard Ciesielski PTB Synchrotron-based EUV metrology at PTB	Multimodal characterization of electrons and excitons in 2D materials and their heterostructures Session 32: Supplier Program Showcase; Session Chair: Take Watanabe (University of Hyogo)	Multimodal characterization of electrons and excitons in 2D materials and their heterostructures 12:10 PM



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#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
						0:15	3:35 PM	3:50 PM
					Nanoscale Chemical Analysis of EUV Resists			
4	P84	Supplier Showcase -2	Sung Park	Molecular Vista	(Invited)			
						0:15	3:50 PM	4:05 PM
					Coffee Break			
						1:00	4:05 PM	5:05 PM
			All		CXRO Facility Tour			
			W/	 orkshop Adjourn	ned for the Day			



#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
	8:30	AM, Wednesday,	June 5, 2024, LBN	L, Berkeley	, CA (Workshop held in-person	only, B	ldg 66 -	317)
			Sessi	on 5: Keynot	te Presentations			
	Sessio	on 6 -8: Source -1 &	Resist and Patterning	g-1; Session 9	9: Poster Session and Reception (Se	ssion 9 i	n Bulidin	g 91)
			Session 5: Keynoto	e - 1; Session Cho	air: Patrick Naulleau (EUV Tech)			
					Breakfast	0:30	8:00 AM	8:30 AM
						0:30	8:30 AM	9:00 AM
					AV Test, Speaker Check-in and Registration			
						0:10	9:00 AM	9:10 AM
		Introduction	Dimitrios Argyriou	LBNL	Welcome to LBNL			
						0:10	9:10 AM	9:20 AM
		Introduction	Vivek Bakshi	EUV Litho, Inc.	Welcome and Announcements			
						0:30	9:20 AM	9:50 AM
5	P4	Keynote	Steven Carson	Intel	High-NA EUV: An Update on Introduction			
					Full Lifetime EUV Cost vs Performance for	0:30	9:50 AM	10:20 AM
5	P5	Keynote	Steve Snyder	Micron	DRAM			
						0:30	10:20 AM	10:50 AM
					New development of EUV materials and MI			
5	P1	Keynote	In-Yong Kang	Samsung	solutions for High NA mask			
					Coffee Break	0:20	10:50 AM	11:10 AM



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# Paper #	Area	Presenter	Company	Title	Duration	Start	Finish				
	Session 6: EUV Sources -1, Session Co-Chairs: Henry Kapteyn (K&M Lab) and Dong Gun Lee (E-Sol)										
					0:15	11:10 AM	11:25 AM				
				Modeling a Discharge-Produced Plasma							
6 P32	Source -1	David Reisman	Energetiq	(DPP) EUV Source (Invited)							
				Nanoscale Coherent Imaging and	0:15	11:25 AM	11:40 AM				
				Functional Characterization using Tabletop-							
6 P37	Source -1	Henry Kapteyn	K&M Labs	Scale Coherent EUV Sources (Invited)							
			Class 5	EUV and Soft-X-Ray Photonic Integrated	0:15	11:40 AM	11:55 AM				
			Photonics	Circuits (XPICs) - Overview and First Results							
6 P40	Source -1	Robert Reidel	GmbH	at 13.5 nm							
					0:15	11:55 AM	12:10 PM				
				Development Of High-Brightness Xe LPP							
6 P31	Source -1	Dong Gun Lee	E-Sol	Source And Its Applications (Invited)							
				Lunch	1:05	12:10 PM	1:15 PM				



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#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
		Session 7.	: Resist and Patterning- 1	; Session Co-Chai	irs: Anuja De Silva (LAM) and Alex Robinson	(IM)		
						0:15	1:15 PM	1:30 PM
					Dry Resist Patterning Readiness Towards			
7	P51	Resist and Patterning -1	Anuja De Silva	LAM	High NA EUV Lithography (Invited)			
						0:15	1:30 PM	1:45 PM
					Advanced Processes for High-NA EUV			
7	P53	Resist and Patterning -1	Congque Dinh	TEL	Lithography (Invited)			
						0:15	1:45 PM	2:00 PM
					Multi-Trigger Resist Patterning towards			
7	P55	Resist and Patterning -1	Alex Robinson	IM	High–NA EUV Lithography (Invited)			
					Enhancement of Photosensitivity and	0:15	2:00 PM	2:15 PM
				Sungkyunkwan	Stability of Sn-12 EUV Resist by Integrating			
7	P56	Resist and Patterning -1	Myung-Gil Kim	University	Photoactive Nitrate Anion			
						0:15	2:15 PM	2:30 PM
				John Hopkins	EUV Lithography Using Zeolitic Imidazolate			
7	P57	Resist and Patterning -1	Michael Tsapatsis	University	Frameworks			
					DOE Accelerate Initiative Project for	0:15	2:30 PM	2:45 PM
				Brookhaven	Accelerating Next-Generation EUV			
7	P59	Resist and Patterning -1	Chang-Yong Nam	National Lab	Photoresist Development (Invited)			
						0:15	2:45 PM	3:00 PM
				Hanyang	Hybrid Multilayer EUV Dry Resist for 1.5 nm			
7	P58	Resist and Patterning -1	Ji-Hoo Seok	University	Technology Node			
					Coffee Break	0:20	3:00 PM	3:20 PM



Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
	Session 8:	Resist and Patterning - 2;	Session Co-Chai	rs: Oleg Kostko (LBNL) and Ryan Miyakawa (LBNL)		
				Sequence Control in Polypeptoid	0:15	3:20 PM	3:35 PM
				Photoresists and Its Effects on Patterning			
P60	Resist and Patterning -2	Chenyun Yuan	Cornell	Performance (Invited)			
					0:15	3:35 PM	3:50 PM
				EUV CAR-NTD with New Developer for			
P67	Resist and Patterning -2	Nishiki Fujimaki	Fuji Film	Chemical Stochastic Defect Reduction			
					0:15	3:50 PM	4:05 PM
				Probing Chemical Transformations in EUV			
P52	Resist and Patterning -2	Oleg Kostko	CXRO	Resists			
				EUV Interference Lithography towards the	0:15	4:05 PM	4:20 PM
				Ultimate Resolution of Photon-based			
P54	Resist and Patterning -2	Iason Giannopoulos	PSI	Nanopatterning (Invited)			
			Chonnam	Non-Alkyl Tin Oxo Cluster of CNU-TOC-	0:15	4:20 PM	4:35 PM
			National	01(4C-C) as Inorganic Resist for EUV			
P62	Resist and Patterning -2	Hyun-Dam Jeong	University	Lithography			
				Evaluation of C-beam Generated EUV	0:15	4:35 PM	4:50 PM
			Kyung Hee	Lightning Source using Mirror and Filter			
P69	Resist and Patterning -2	Umesh Balaso Apugade	University	Technique			
					0:15	4:50 PM	5:05 PM
				Performance of the Berkeley MET Using a			
P13	Resist and Patterning -2	Ryan Miyakawa	CXRO	Stand-Alone Plasma Source			
				Break / Move to Poster Session Location	0:40	5:05 PM	5:45 PM
	P60 P67 P52 P54 P62	P60 Resist and Patterning -2 P67 Resist and Patterning -2 P52 Resist and Patterning -2 P54 Resist and Patterning -2 P62 Resist and Patterning -2 P69 Resist and Patterning -2	P60 Resist and Patterning -2 Chenyun Yuan P67 Resist and Patterning -2 Nishiki Fujimaki P52 Resist and Patterning -2 Oleg Kostko P54 Resist and Patterning -2 Iason Giannopoulos P62 Resist and Patterning -2 Hyun-Dam Jeong P69 Resist and Patterning -2 Umesh Balaso Apugade	Session 8: Resist and Patterning - 2; Session Co-Chai P60 Resist and Patterning - 2 Chenyun Yuan Cornell P67 Resist and Patterning - 2 Nishiki Fujimaki Fuji Film P52 Resist and Patterning - 2 Oleg Kostko CXRO P54 Resist and Patterning - 2 Iason Giannopoulos PSI Chonnam National P62 Resist and Patterning - 2 Hyun-Dam Jeong University P69 Resist and Patterning - 2 Umesh Balaso Apugade University	Session 8: Resist and Patterning - 2; Session Co-Chairs: Oleg Kostko (LBNL) and Ryan Miyakawa (Sequence Control in Polypeptoid Photoresists and Its Effects on Patterning Performance (Invited) EUV CAR-NTD with New Developer for Chemical Stochastic Defect Reduction Probing Chemical Stochastic Defect Reduction Probing Chemical Transformations in EUV Resists EUV Interference Lithography towards the Ultimate Resolution of Photon-based Nanopatterning (Invited) PSI Nanopatterning (Invited) P62 Resist and Patterning -2 Hyun-Dam Jeong University Lithography EVALUATION Resist For EUV Lightning Source using Mirror and Filter University Technique P69 Resist and Patterning -2 Ryan Miyakawa CXRO Stand-Alone Plasma Source	Session 8: Resist and Patterning - 2; Session Co-Chairs: Oleg Kostko (LBNL) and Ryan Miyakawa (LBNL) Sequence Control in Polypeptoid Photoresists and Its Effects on Patterning Photoresists and Its Effects on Patterning Performance (Invited) Cornell Performance (Invited) Corne	Session 8: Resist and Patterning - 2; Session Co-Chairs: Oleg Kostko (LBNL) and Ryan Miyakawa (LBNL) Sequence Control in Polypeptoid Photoresists and Its Effects on Patterning October Photoresists and Its Effects on Patterning Performance (Invited) P60 Resist and Patterning - 2 Chenyun Yuan Cornell Performance (Invited) EUV CAR-NTD with New Developer for Chemical Stochastic Defect Reduction P70 Resist and Patterning - 2 Oleg Kostko CXRO P70 Resist and Patterning - 2 Oleg Kostko CXRO P70 Resist and Patterning - 2 Iason Giannopoulos P51 Resist and Patterning - 2 Iason Giannopoulos P52 Resist and Patterning - 2 Iason Giannopoulos P53 Resist and Patterning - 2 Iason Giannopoulos P64 Resist and Patterning - 2 Iason Giannopoulos P55 Resist and Patterning - 2 Iason Giannopoulos P56 Resist and Patterning - 2 Iason Giannopoulos P57 Resist and Patterning - 2 Iason Giannopoulos P58 Resist and Patterning - 2 Iason Giannopoulos P59 Resist and Patterning - 2 Iason Giannopoulos P50 Resist and Patterning - 2 Iason Giannopoulos P60 Resist and Patterning - 2 Iason Giannopoulos



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# Paper #	# Area	Presenter	Company	Title	Duration	Start	Finish
		Session 9: Poste	er Session and Rece	ption, Session Chair: Vivek Bakshi			
					1:30	5:45 PM	7:15 PM
				Poster Session and Reception			
			Hanyang	Study of Enhancing Etching Performance of			
9 P20	Poster Session	Seungho Lee	University	Pt-based Absorber Material for EUV Mask			
		-		Experimental Investigation of the Mask			
			Hanyang	Diffraction Obstructed by the Critical-sized			
9 P21	Poster Session	Seungchan Moon	University	Sn Particles on EUV Pellicle			
				Energetiq Source Update: Spherically			
9 P39	Poster Session	Kosuke Saito	Energetiq	Shaped Source for High NA Metrology			
			- 8-1-4	Enhanced EUV Lighting with Focusing			
			Kyung Hee	Electrode Adapted C-beam Irradiation			
9 P41	Poster Session	Iksu Kim	University	Technique			
				Tacting Digitary of Entrana ultraviolet			
9 P42	Poster Session	Wooram Kim	KRISS	Testing Platform of Extreme-ultraviolet (EUV) Materials and Optical Components			
				Tetrahydroxy-tetramethyl-			
			Chonnam	cyclotetrasiloxane as an Inorganic EUV			
			National	Resist: Exploring Cross-Linking Mechanisms			
9 P61	Poster Session	Jiyoung Bang	University	and Lithography Performance			
				The Investigation of the Effect of Electron			
				Beam and Extreme Ultraviolet Irradiation			
			Chonnam	on Dibenzyltin Diacetate Thin Film Using			
0 003	Dantau Carrier	Uhan ala V	National	Local Analysis and Quantum Chemical			
9 P63	Poster Session	Hyeok Yun	University	Calculations			
			Chonnam	Synthesis and Characterization of Novel			
2 200			National	Two-in-One Type Siloxane Molecule			
9 P64	Poster Session	Wonchul Kee	University	Photoresist for EUV Lithography			



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#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
					Enabling High-throughput Characterization			
					of Outgassing and Total Electron Yield for			
9	P65	Poster Session	Bernhard Lüttgenau	CXRO	Model EUV Resist Materials			
					Investigating Influence of Electron Affinity			
9	P66	Poster Session	Honggu Im	CXRO	on Electron Emission in EUV Photoresists			
9	P68	Poster Session	Ji-Hoo Seok	Hanyang University	Dry Development Process for Vertically Tailored Hybrid Multilayer EUV Photoresist			
9	P91	Poster Session	Alessandro Ruocco	FS Dynamics	Plasma Modelling at FS Dynamics			
					Blazed, Variable-line-space Reflection Gratings for 13.5-nm Optics Fabricated at			
9	P92	Poster Session	Samuel Gleason	Inprentus, Inc.	Inprentus			
					15 11 5			
				Workshop Adjour	rned for the Day			



# Paper	# Area	Presenter	Company	Title	Duration	Start	Finish
	8:30 AM, Thursday	, June 6, 2024, LBNL,	Berkeley, CA	(Workshop held in-person only, Bu	uilding 6	6 - 316)	
		Session 10: Key	ynote -2; Se	ession 11: EUV Sources-2			
		Session 12	2-13: Mask /	Optics / Metrology			
				Harry Levinson (HJL Lithography)			
				Breakfast	0:30	8:30 AM	9:00 AM
					0:10	9:00 AM	9:10 AM
	Introduction	Vivek Bakshi	EUV Litho, Inc.	Welcome and Announcements			
					0:30	9:10 AM	9:40 AM
				The Next Step in Moore's Law: High NA			
10 P3	Keynote	Jan van Schoot	ASML	EUV Imaging and Overlay Performance			
					0:30	9:40 AM	10:10 AM
				Pushing for record reflectivities for short			
10 P2	Keynote	Marcelo Ackermann	UTewnte	wavelength multilayers – EUV and beyond			
				Current Status and Technical Issues of the	0:30	10:10 AM	10:40 AM
			University of	EUVL and Prospect for the Next Generation			
10 P6	Keynote	Takeo Watanabe	Hyogo	EUVL			
					0:20	10:40 AM	11:00 AM
				Coffee Break			
	Sessio	n 11: EUV Sources -2 ; Sess	ion Chairs: Felic	ie Albert (LLNL) and Jeroen van Tilborg (LBNL)		
				Laser-plasma Acceleration: Next	0.15	11:00 AM	11·15 AM
				Generation X-ray Light Sources for	0.13	11.007.11	11.15 / ((V)
11 P34	Source -2	Felicie Albert	LLNL	Industrial Applications (Invited)			
				Compact Radiation Sources from Laser-	0:15	11:15 AM	11:30 AM
				Plasma Accelerators at LBNL's BELLA Center			
11 P33	Source -2	Jeroen van Tilborg	LBNL	(Invited)			
				Commercializing Laser-Wakefield	0:15	11:30 AM	11:45 AM
				Accelerator Systems and Their Applications			
11 P36	Source -2	Steve Milton	Tau Systems	(Invited)			



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#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
						0:15	11:45 AM	12:00 PM
					Tm:YLF lasers for driving EUV Sources			
11	P35	Source -2	Zbynek Hubka	LLNL	(Invited)			
						0:15	12:00 PM	12:15 PM
					High-average-power ERL FEL for EUV			
11	P43	Source -2	Dinh Nguyen	Xlight	Lithography (Invited)			
				Tsinghua	The Recent Process on Steady-State	0:15	12:15 PM	12:30 PM
11	P38	Source -2	Zhilong Pan	University	Microbunching EUV Light Source Project			
						1:30	12:30 PM	2:00 PM
					Lunch and Workshop Steering Committee			
					Meeting (Closed)			



#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish			
	Session 12: EUV Mask / Optics /Metrology - 1; Session Chairs: Katrina Rook (Veeco) and Michael Lam (Synopsys)										
						0:15	2:00 PM	2:15 PM			
					Status and Outlook of EUV optics at ZEISS						
12	P22	Mask /Optics/Metrology	Martin Kaumanns	Carl Zeiss	(Invited)						
					Thickness-dependent optical constants of	0:15	2:15 PM	2:30 PM			
			Richard Ciesielski, Samira		silicon thin films within the EUV spectrum:						
12	P24	Mask /Optics/Metrology	Naghdi	РТВ	insights and implications for EUVL systems						
						0:15	2:30 PM	2:45 PM			
					Ion Beam Deposition over Larger Form-						
12	P15	Mask /Optics/Metrology	Katrina Rook	Veeco	Factor EUV Mask Blanks (Invited)						
					Efforts in the Development of EUV Masks	0:15	2:45 PM	3:00 PM			
					within the Context of a Merchant Mask						
12	P19	Mask /Optics/Metrology	Hiroki Deguchi	DNP	Shop						
						0:15	3:00 PM	3:15 PM			
					Computational Lithography Solutions for						
12	P23	Mask /Optics/Metrology	Michael Lam	Synopsys	High NA EUV with Mask Stitching (Invited)						
					Coffee Break	0:20	3:15 PM	3:35 PM			



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#	Paper #	Area	Presenter	Company	Title	Duration	Start	Finish
		Sossion 12: EU	/ Mack / Ontice /Matrol	nay 2: Sossion Cl	hairs: Marcus Benk (LBNL) and Sangsul Lee (I	DOSTECU)		
		Jessioii 15. EU	v iviusk / Optics / ivietroit	ogy - 2, session Ci	ians. Marcus Benk (LBNL) and Sangsur Lee (1	ОЗТЕСП		
						0:15	3:35 PM	3:50 PM
13	P11	Mask /Optics/Metrology	Stuart Sherwin	EUV Tech	EUV Tech n/k Tool			
						0:15	3:50 PM	4:05 PM
					Effects of EUV Multilayer Roughness in High			
13	P12	Mask /Optics/Metrology	Luke Long	EUV Tech	NA EUV Lithography			
						0:15	4:05 PM	4:20 PM
					Mask-side Hyper-NA imaging on the SHARP			
13	P14	Mask /Optics/Metrology	Marcus Benk	CXRO	EUV mask microscope			
						0:15	4:20 PM	4:35 PM
					Integrating Actinic EUV Research with			
13	P18	Mask /Optics/Metrology	Sangsul Lee	POSTECH	Advanced Analytical Technologies (Invited)			
						0:05	4:35 PM	4:40 PM
				SDIE				
			Harry Levinson	SPIE	JM3			
						0:10	4:35 PM	4:45 PM
			Vivek Bakshi	EUV Litho. Inc.	Announcements			
			Workshop Adiou	rned. Leave fo	or Off-Site Workshop Dinner			



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